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Application Number	09/905,718				
Filing Date	May 16, 2002				
First Named Inventor	Watts et al.				
Group Art Unit	1762				
Examiner Name	Bernard D. Pianalto				
Attorney Docket Number	PA27/UTS-26-03q12				

		U.S. Patent Do		J	Date of Publication of	Pages, Columns, Lines,
Examiner Initials*	Cite No. ¹	Number	Kind Code ² (if known)	Name of Patentee or Applicant of Cited Document	Cited Document MM-DD-YYYY	Where Relevant Passages or Relevant Figures Appear
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Attorney Docket Number	PA27/UTS-26-03q12					

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First Named Inventor	Watts et al.					
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Examiner Name	Bernard D. Pianalto					
Attorney Docket Number	PA27/UTS-26-03q12					

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ATEM !	PARTY : -	Application Number	09/905,718
	INFORMATION DISCLOSURE	Filing Date	May 16, 2002
*	STATEMENT BY APPLICANT	First Named Inventor	Watts et al.
		Group Art Unit	1762
	(use as many sheets as necessary)	Examiner Name	Bernard D. Pianalto

Attorney Docket Number

PA27/UTS-26-03q12

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COLUMN C. LINGS	Application Number	09/905,718
INFORMATION DISCLOSURE	Filing Date	May 16, 2002
STATEMENT BY APPLICANT	First Named Inventor	Watts et al.
	Group Art Unit	1762
(use as many sheets as necessary)	Examiner Name	Bernard D. Pianalto

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Filing Date	May 16, 2002				
First Named Inventor	Watts et al.				
Group Art Unit	1762				
Examiner Name	Bernard D. Pianalto				
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